

Title (en)

METHOD OF CONTINUOUSLY REGENERATING AN ELECTROLESS-PLATING BATH AND DEVICE FOR CARRYING OUT THE METHOD

Publication

EP 0192310 B1 19900822 (EN)

Application

EP 86200247 A 19860219

Priority

NL 8500474 A 19850220

Abstract (en)

[origin: EP0192310A1] An electroless plating bath is continuously regenerated by means of reverse osmosis and selective membranes are used which yield a high retention of metal complexes, complexing agents and surfactants and a low retention of the monovalent anions to be removed, for example, nitrate, formate anions and bicarbonate anions in the case of a copper-plating bath.

IPC 1-7

C23C 18/16

IPC 8 full level

C23C 18/31 (2006.01); **C23C 18/16** (2006.01)

CPC (source: EP)

C23C 18/1617 (2013.01)

Citation (examination)

DE 3022962 A1 19810212 - HITACHI LTD

Cited by

US5328616A; US4865877A; EP1199386A3; CN109609933A; EP0274387A3

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